

## IN THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (currently amended)      A method, comprising:  
  
    applying a layer of a dielectric material comprising fluorescent material on a first substrate comprising a conductor;  
  
    forming, with an imprinting tool, at least one trench at least partially through the dielectric material to the first substrate;  
  
    directing radiation in a first range of wavelengths from a radiation source to the trench; ~~and~~  
  
    detecting radiation in a second range of wavelengths emitted from dielectric material at the bottom of the trench; and  
  
    determining, from the detected radiation, whether the trench has been successfully formed and the bottom of the trench is substantially free from dielectric material of the layer of dielectric material, or whether the trench has not been successfully formed and the bottom of the trench has an undesired amount of dielectric material of the layer of dielectric material.
2. (original)    The method of claim 1, wherein the fluorescent material comprises less than about 10 percent of the dielectric material.
3. (original)    The method of claim 1, wherein the fluorescent material comprises less than about 2 percent of the dielectric material.
4. (original)    The method of claim 1, wherein the first range of wavelengths comprises a range of ultraviolet radiation.

5. (original) The method of claim 1, wherein the second range of wavelengths comprises a range of visible light.

6. (original) The method of claim 1, further comprising determining that formation of the trench has failed in response to detecting an intensity of radiation in the second range of wavelengths emitted from dielectric material at the bottom of the trench in excess of a threshold intensity.

7. (currently amended) A method, comprising:

pressing an imprinting tool into a dielectric material comprising fluorescent material;

directing radiation in a first range of wavelengths from a radiation source to the imprinting tool; ~~and~~

detecting radiation in a second range of wavelengths emitted from material on the imprinting tool; and

determining, from the detected radiation, whether the tool has been used with substantially no dielectric material stuck to the tool after use and does not require cleaning, or whether the tool has enough dielectric material stuck to the tool that maintenance of the tool should be performed.

8. (original) The method of claim 7, wherein the first range of wavelengths comprises ultraviolet radiation.

9. (original) The method of claim 7, wherein the second range of wavelengths comprises visible light.

10. (original) The method of claim 7, further comprising maintaining the imprinting tool in response to detecting an intensity of radiation in the second range of wavelengths emitted from material on the imprinting tool in excess of a threshold intensity.

11. – 15. (canceled)

16. (new) The method of claim 6, wherein further processing is performed to remove dielectric material from the bottom of the trench after determining that formation of the trench has failed.